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# **Large area crystalline Weyl semimetal with nano Au film based micro-fold line array for THz detector**

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The advancement of 6G technology relies on the development of high-performance terahertz detectors that can operate at room temperature. These detectors are crucial for Internet of Things (IoT) applications, which require sensitive environmental sensing and efficient reception of 6G signals. One significant research focus is on detection technology with high responsiveness and low equivalent noise power for 6G signals, which experience high losses in the air. To meet the demand for ultra-sensitive detectors in 6G technology, we have employed several techniques. Firstly, we prepared a large area of Weyl-semimetal layer through magnetron sputtering. Secondly, we obtained a high-quality Weyl-semimetal active layer by carefully controlling the annealing conditions. Next, a thin nano-Au layer was introduced as a micro-cavity reflection layer to enhance the device's detection rate. Additionally, we incorporated an electromagnetic induction well to improve carrier confinement and enhance the detection sensitivity. This proposed high-performance terahertz detector, with its potential for industrial production, offers a valuable technical solution for the advancement of 6G technology.

**micro-cavity, Weyl semimetal, crystalline thin film, THz device**

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## **1 Introduction**

The maturity of Internet of Things (IoT) technology has led to significant growth in IoT-based system applications. This trend is particularly evident in various areas such as personal wearable devices, intelligent transportation systems for vehicle networking, and medical services to the financial industry. With the intelligent 6G technology offering advantages like broad bandwidth and high transmission rates, there are strong prospects for applying artificial intelligence (AI) at the network edge  $[1-3]$  $[1-3]$ . In this context, edge intelligence technology has emerged as a convergence of AI, communication, and edge computing technologies, enabling innovative solutions and facilitating efficient data processing at the network edge. The success of edge intelligence applications in 6G network technology relies on high-performance terahertz detectors. These detectors are essential for IoT scenarios, as they enable sensitive environmental sensing and efficient reception of 6G signals, which experience significant losses in the air. Therefore, it is crucial to research detection technology that offers high responsiveness and low equivalent noise power for 6G signals. This research focuses on optimizing the performance of terahertz detectors,

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ensuring they can effectively capture and process weak 6G signals while minimizing noise interference [[4–](#page-8-2)[7\]](#page-8-3).

The current sensitive detection technology of terahertz waves at room temperature includes the detection technology based on photoelectric signals and the detection technology based on thermoelectric signals. The detection technology based on thermoelectric signals utilizes the thermal effect caused by terahertz waves, resulting in changes in the phase change or electrical conductivity of the active layer material, enabling the detection of terahertz signals. The thermoelectric signal detection method generally has a slower detection rate. On the other hand, the photoelectric signal detection method utilizes the interaction between terahertz photons and the active layer material to generate photocurrent for detection. Due to the low energy of terahertz photons, materials with nearly zero band gap are required to induce photocurrent. Additionally, in order to reduce noise, the active layer materials should have strong absorption capabilities for low-energy photons. As a result, Weyl-semimetallic materials with topological Weyl-point energy band structures have been gaining attention from researchers [[8–](#page-8-4)[10\]](#page-8-5).

The close-to-zero band gap of the Weyl semimetal energy band system allows it to effectively absorb terahertz waves with low photon energies. When THz waves are absorbed, the carriers in Weyl semimetal move towards the vicinity of the Weyl point. This leads to an enhanced displacement current response, which is associated with the diverging Berry curvature  $[11-13]$  $[11-13]$  $[11-13]$ . As a result, the Weyl semimetal exhibits an increased photocurrent response for terahertz waves with low photon energies. This makes it more suitable for detecting such terahertz waves with improved sensitivity and reduced noise compared to other materials [\[14\]](#page-8-8). To achieve a large area for efficient active layer preparation, magnetron sputtering was chosen as the active layer processing method. The carrier generation and transport efficiency increases dramatically after the crystallization of the film, and annealing is a more ideal crystallization method for magnetron-sputtered films [\[15\]](#page-8-9). We investigated the preparation of high-quality crystalline films using different annealing temperatures and different annealing times.

When subwavelength microstructures are added to the surface of the active layer, it can induce a localized surface plasmon (LSP) effect. This effect occurs when the incident signal, such as a 6G signal in the terahertz band, interacts with both the active layer material and the array of subwavelength microstructures on its surface. The interaction between the signal and the microstructures can lead to enhanced light-matter interactions, improved signal propagation, or other specific functionalities [\[16](#page-8-10)[–18](#page-8-11)]. Adding subwavelength structures to the active layer can confine the THz wave (6G signal) to a small region, leading to enhanced contact between the signal and the active layer. This confinement greatly increases the photocurrent and improves the responsiveness of the detector. Laser direct writing technology allows for the creation of two-dimensional (2D) microstructures on the device surface with minimal limitations. It is capable of processing structures with line widths of approximately 20 microns, which is suitable for terahertz functional devices in terms of accuracy. Laser direct writing is a simple and cost-effective method for achieving precise surface patterns on the micron and 100-micron scale without the need for additional materials or causing additional losses. This technique is discussed in further detail as a viable approach for creating these patterns in the references provided. To increase the interaction between the terahertz field and the active layer in the smallest scale, a micro-cavity structure can be introduced to take advantage of the reflection of terahertz waves from the metal layer and the large number of free carriers in the metal layer, a micro-reflection cavity can be formed between the Weyl semi-metal layer and the metal layer, which can further enhance the detection effect of the device by re-incidence with the active layer after THz reflection. Therefore, we added a nanofilm Au layer in the design, as a reflection layer of terahertz waves can also collect carriers and increase the detected photocurrent. In addition, a subwavelength microstructure is prepared between the metal layer and the Weyl metal layer by femtosecond laser direct writing technique, and an electromagnetic induction well (EIW) is formed near the structure to transfer the carriers in the metal layer to the semimetal layer and confine them around the subwavelength structure, so that an EIW with confined carriers is formed around the half-metal microstructure, and this region where a large number of carriers gather changes the dielectric constant of the material itself, which is more sensitive to the incident terahertz wave. This region of massive carrier aggregation changes the dielectric constant of the material itself and makes it more sensitive to the response of incident terahertz waves, further increasing the detection efficiency of terahertz waves.

In summary, to realize the requirement of edge-smart ultrasensitive detectors for 6G IoT technology, we have prepared large-area Weyl-semi-metal layers by magnetron sputtering, and obtained high-quality Weyl-semimetal active layers by controlled annealing conditions. Additionally, nanofilm Au layers were prepared as microcavity reflection layers to enhance the device detection rate. Finally, 2D surfaceized micropattern arrays were created using laser direct writing technique. The resulting terahertz detector is high-performance and has the potential for industrial production. Our devices have the potential to contribute to the development of edge intelligence for 6G IoT technology.

#### **2 Experimental procedure**

To obtain high-quality  $WTe_2$  films, we followed a procedure

involving the preparation of  $WTe<sub>2</sub>$  films on silicon substrates using magnetron sputtering. Subsequently, the devices were transferred to an annealing table that was protected by nitrogen gas. The devices were then heated to various temperatures and held for different durations to complete the annealing process. Finally, the annealing quality was assessed by characterizing the Raman spectra under different annealing conditions using Raman spectroscopy. The prepared film area is 5 mm  $\times$  10 mm. The thickness of Au layer and WTe<sub>2</sub> layer are 36 nm and 1.08  $\mu$ m. The WTe<sub>2</sub> layer and Au layer were prepared by the following steps. At first, the air pressure was reduced to 9  $\times$  10<sup>-4</sup> Pa, and injects argon into the cavity. The WTe<sub>2</sub> target is coated using radio frequency (RF) drive mode, and the Au target is coated using direct current (DC) drive mode. For the WTe<sub>2</sub> layer, the parameters were set as follows. The argon flow rate of 50 standard cubic centimeter per minute (SCCM), power of 100 W, and duration time of 600 s was set. For the Au layer, the argon flow rate, current and duration time of 15 SCCM, 0.2 A, and 90 s were set. First, we characterized the properties of the films using X-ray photoelectron spectroscopy  $(XPS)$  in [Figure 1\(](#page-2-0)a) and (b), and the results showed that the  $4p_1$  and 4s feature peaks of the W element of WTe<sub>2</sub> are located at 490.5 and 593.6 eV. The  $3d_3$  and  $3d_5$  feature peaks of the Te element are located at 583.3 and 572.9 eV. The thickness of Au layer and WTe<sub>2</sub> layer are shown in [Figure 1](#page-2-0) (c) and (d).

We conducted annealing experiments on  $WTe<sub>2</sub>$  films with the same coating parameters and thickness results using a nitrogen-filled gas annealing platform. The crystallization of the  $WTe<sub>2</sub>$  films was characterized at different annealing temperatures. By referring to the relationship between Raman spectra and crystallization provided in the literature [\[19](#page-8-12),[20\]](#page-8-13) (see [Figure 2](#page-3-0)(a)), it can be concluded that a narrower Raman peak position and a higher relative intensity indicate a better crystallization effect. Applying this principle, we determined that the optimal crystallization of the film is achieved at an annealing temperature of 150°C. However, as the temperature exceeds 200°C, the crystallization effect gradually diminishes. This decrease in crystallization may be attributed to the disruption of WTe<sub>2</sub> molecular bonds at high temperatures, resulting in poor crystallization.

[Figure 2\(](#page-3-0)b) displays the complex conductivity of the  $WTe<sub>2</sub>$ nanofilm at room temperature. To analyze the frequency dependence of conductivity, we employed the ordinary Drude equation for fitting purposes [\[21\].](#page-8-14)

$$
\sigma(\omega) = \sigma_0 \frac{1}{1 - i\omega \tau},\tag{1}
$$

where *ω* indicates the frequency of the THz wave, *τ* is the quasiparticle relaxation time, and  $\sigma_0$  is DC conductivity. The results of the complex conductivity in the terahertz band show the best complex conductivity parameters at the preferred annealing temperature, i.e., 60 min at 150°C. The WTe<sub>2</sub> films obtained under this condition are more suitable for use as devices in the THz band.

The current probe platform and terahertz time-domain spectrum system are shown in [Figure 3](#page-3-1)(a) and (b). Therefore, we chose to anneal the  $WTe<sub>2</sub>$  films prepared by magnetron sputtering at 150°C. In addition, we also selected the annealing time, and the best effect was obtained at 60 min.To



<span id="page-2-0"></span>**[Figure 1](#page-2-0)** (Color online) Characterization of WTe<sub>2</sub> thin films. (a and b) XPS results of WTe<sub>2</sub> thin films. (c) SEM of Au film thickness. (d) SEM of WTe<sub>2</sub> film thickness.



<span id="page-3-0"></span>**[Figure 2](#page-3-0)** (Color online) Characterization results for different annealing temperatures. (a) Raman spectrum. (b) Complex conductivity in THz frequency.

further confirm the influence of crystalline films on terahertz detection after annealing, we tested the complex conductivity of several films with different annealing temperatures at the same annealing time in the terahertz frequency range. The test system is a photoconductive antenna (PCA) transmit and receive-based terahertz time-domain spectroscopy system. The THz beam was not focused on the sample. The laser used in our experiment with the central wavelength of 780 nm, the repetition frequency of 80 MHz, the pulse width of 90 fs, and the spectral width of 7 nm.

In the following, we prepared Au electrodes with the same pitch (3 mm) on crystalline thin film devices under different annealing conditions, respectively, used 0.1 THz source incidence, and examined the detection effect of the films on terahertz waves under different conditions.

We employed a method of comparing light and dark currents, utilizing light current excitation, to assess the detection capability of the device. The terahertz detector is positioned at the center of the probe platform, and two robust tungsten steel probes (with a needle tip size of  $10 \mu m$ ) are utilized to establish contact with the metal electrodes of the device. These probes are connected to a digital source meter, specifically the Keithley 2400. As for the terahertz emitter, we utilized terahertz IMPATT diodes, specifically the TeraSense IMPATT diodes model at 0.1 THz, with a maximum output power of 70 mW. Prior to the experiment, we measured the output power using a THz power meter (ELVA-1 DPM). It is worth noting that the total area of our device exceeds the diffraction-limited area.



<span id="page-3-1"></span>**[Figure 3](#page-3-1)** (Color online) Schematic diagram of the THz test system. (a) Current probe platform. (b) Terahertz time-domain spectrum system.

[Figure 4](#page-4-0) illustrates the detection performance, encompassing the total noise, responsivity, noise equivalent power (NEP), and detectivity  $(D^*)$  for the WTe<sub>2</sub> thin film devices under various annealing temperatures and times. Specifically, we consider the following annealing conditions: 150°C for 30 min, 150°C for 60 min, 200°C for 30 min, and an unannealed device as a reference. Based on the results of the detection experiments, it is evident that the annealing condition of 150°C for 60 min yields the most favorable outcomes. This aligns with the findings of the Raman characterization, as under this specific annealing condition, the film demonstrates more ideal crystallization, resulting in higher carrier mobility within the crystalline film of the same material. Consequently, this leads to a larger bright current and improved detection. Furthermore, the results indicate that annealing at 200°C for 30 min outperforms annealing at 150°C for the same duration. This can be attributed to the fact that high temperatures cause the breaking of certain molecular bonds, thereby enhancing detection at 150°C. To further demonstrate the photo-electrical conversion capability of their detectors, we also calculate the photoresponsivity  $(R_A)$ , NEP, and  $D^*$  through a light-dark current comparison.

 $R_A$ , NEP, and  $D^*$  are defined as [[22](#page-8-15)[,23](#page-8-16)]

$$
R_{A} = I/P,
$$
  
NEP =  $v_{n} / R_{A}$ ,  
and  

$$
D^* = \sqrt{S} / NEP,
$$
 (2)

<span id="page-3-2"></span>where  $I$  is the photocurrent of the device.  $P$  is the incident THz power, and *S* is the effective detection area of the detector. And  $v_n$  is the noise voltage as shown in [Eq. \(2\)](#page-3-2) [\[23\]](#page-8-16).

$$
v_{\rm n} = \sqrt{{v_{\rm t}}^2 + {v_{\rm b}}^2} = \sqrt{4k_{\rm B}Tr + 2qI_{\rm d}r^2},\tag{3}
$$

where  $k_B$ , *T*, *r*, *q*, and  $I_d$  are Boltzmann's constant, the detector's absolute temperature, resistance value, elementary charge, and dark current, respectively.

With different voltage at room temperature for the incident THz frequency of 0.1 THz. The  $R_A$  linearly increases with



<span id="page-4-0"></span>**[Figure 4](#page-4-0)** (Color online) Results of terahertz detection performance parameters for WTe<sub>2</sub> films. (a) Device noise. (b) Sensitivity. (c) Equivalent noise power. (d) Detectivity *D*\*.

the applied voltage, due to the nonequilibrium electrons proportional to the drift velocity. With the applied voltage of 20 V, the  $R_A$  for 150°C, 60 and 30 min annealing time devices, and 200°C 30 min annealing time devices are 0.6, 0.3 and 0.21 A/W, which is higher than the unannealed reference devices 0.17 A/W. The NEP are 47.78, 50.55, 56.61 and 82.89 pW/Hz<sup>1/2</sup>. The  $D^*$  of the rating and spiral electrode devices are 9.4, 8.8, 7.9, and  $5.4 \times 10^9$  cm Hz<sup>1/2</sup>/W.

### **3 Results and discussion**

We conducted simulations to analyze the surface electric field distribution and surface current distribution of different microstructure arrays for an incident terahertz source at 0.1 THz. The simulation results for devices with spacing of 70 and 140 μm are presented in Figures [5](#page-5-0) and [6,](#page-5-1) respectively. Our results indicate that, for the same 2D pattern but with different spacing, the results demonstrate that when the spacing approaches 100 μm, the superimposed results align more closely with the resonant frequency of the LSP effect. This suggests that devices operating at or near the resonant frequency can effectively confine more terahertz waves due to the enhanced localized equipartition excitonic effects introduced by the microstructure arrays. Consequently, the simulated results reveal stronger surface electric fields.

Furthermore, the strength of surface currents reflects the extent of carrier aggregation, and these currents become more pronounced as the microstructure array parameters approach the size of LSP resonance.

Furthermore, when comparing various 2D patterns with the same line spacing, it is observed that the folded line array with 90° angles exhibits a greater number of regions for restricting terahertz waves in comparison to the linear array. In addition to the regions near the lines, the regions associated with each folded angle can also be utilized for limiting terahertz waves. Consequently, the regions available for restricting terahertz waves are more extensive. This observation is supported by the simulation results, which indicate that the folded line microstructure array possesses larger regions for limiting terahertz waves. Moreover, the surface electric field, which is responsible for restricting the strength of the terahertz field, is also larger in the folded line microstructure array. Additionally, the generated surface current is also greater in this array.

Finally, the impact of metal layers is taken into consideration. The metal nanofilm serves two primary functions: Firstly, it forms a microcavity between the active semimetal layer and the Au layer, enhancing the interaction between the incident terahertz waves and the active layer. Crystallized Weyl semi-metal exhibits a stronger ability to absorb lowenergy terahertz photons and generate photocurrents.



<span id="page-5-0"></span>**[Figure 5](#page-5-0)** (Color online) Simulation of the device with 70 μm line spacing. (a) Electric field distribution of folded line array with Au nanofilm. (b) Electric field distribution of linear array with Au nanofilm. (c) Electric field distribution of linear array without Au nanofilm. (d) Electric field distribution of linear array without Au nanofilm. (e) Surface current distribution of folded line array with Au nanofilm. (f) Surface current distribution of linear array with Au nanofilm. (g) Surface current distribution of folded array without Au nanofilm. (h) Surface current distribution of linear array without Au nanofilm.



<span id="page-5-1"></span>**[Figure 6](#page-5-1)** (Color online) Simulation of 140 μm line pitch device. (a) Electric field distribution of folded line array with Au nanofilm. (b) Electric field distribution of linear array with Au nanofilm. (c) Electric field distribution of linear array without Au nanofilm. (d) Electric field distribution of linear array without Au nanofilm. (e) Surface current distribution of folded line array with Au nanofilm. (f) Surface current distribution of linear array with Au nanofilm. (g) Surface current distribution of folded array without Au nanofilm. (h) Surface current distribution of linear array without Au nanofilm.

Additionally, the enhancement of displacement current response near the Weyl point is more significant. Therefore, the introduction of the microcavity structure enhances the efficiency of generating photocurrents in the Weyl semimetal layer. Secondly, the addition of metal nanofilms with subwavelength microstructures creates EIWs at the intersection of the metal and semimetal layers. This structure confines the free carriers in the metal layer to the EIW, greatly increasing the carrier concentration in the semimetal active layer. Consequently, the combination of these two factors explains the confinement effect of the metal layer device on the terahertz field and the significant enhancement of the surface current, as observed in the simulation results. Based on this, we have designed the preferred parameters for a 2D folded array with a 70 μm structural spacing of the Auplated reflective layer. Since the processing parameters for the crystalline  $WTe_2$  film have been determined, the subsequent experiments are conducted using the preferred  $WTe<sub>2</sub>$ crystalline film to fabricate the device. The process involves preparing an Au nanofilm through magnetron sputtering on Si as a reflection layer, followed by the preparation and annealing of WTe<sub>2</sub> at  $150^{\circ}$ C for 60 min. Finally, an Au electrode layer with an electrode size of 1 mm  $\times$  10 mm and a spacing of 3 mm is processed on the device surface.

[Figure 7](#page-6-0) illustrates the ablated folded line groove array on a thin film-based Si substrate. It consists of the WTe<sub>2</sub> active layer (1.08 μm thick) and the Au reflective layer (36 nm thick), sequentially grown on the Si substrate (400 μm thick). For the laser ablation process, a femtosecond laser with a repetition frequency of 50 kHz, pulse width of 433 fs, average output power of 65 mW, and spot radius of 10 μm is utilized. The exposure time is controlled by an electronic shutter with an on-off time of 0.1 ms, resulting in five pulses at the minimum on-off time. The sample is positioned on a computer-controlled 3D translation stage with a minimum displacement of 20 μm. The scanning speed is precisely controlled to fabricate the desired pattern in the films. The scanning speeds of the 3D stage are 10 and 8 mm/s for the  $WTe<sub>2</sub>$  film and the WTe<sub>2</sub> sandwiched Au film, respectively. The detection setup is the same as the one used for the  $WTe<sub>2</sub>$ films, as shown in Figure  $3(a)$ . The femtosecond laser direct writing achieves a line width of 20 μm.

[Figure 8](#page-6-1) presents the results of the terahertz detection performance for devices with line spacings of 70 and 140 μm, with and without the Au layer, at room temperature. The  $R_A$ , NEP, and  $D^*$  are also calculated by comparing the light-dark current to demonstrate the photo-electrical conversion capability of the detectors.

For devices that have varying line spacing, the closer the line spacing and line width are to 100 μm, the closer the size aligns with the resonant frequency of the LSP effect. Consequently, devices that are close to the resonant frequency experience a stronger LSP effect introduced by the microstructured array, resulting in a greater confinement of terahertz waves. The degree of carrier aggregation is reflected in the surface current, which is stronger when the microstructured array parameters are closer to the LSP resonant frequency. This is evident in the higher sensitivity, smaller NEP, and larger *D*\* values. For devices coated with an Au layer, the engraved microstructure introduces the enhanced internal wave (EIW) effect and the micro-cavity effect reflected from the Au layer. The combination of these two effects significantly enhances the interaction between the device's active layer and the terahertz wave. Additionally, the carrier aggregation effect generated by EIW further enhances the surface carrier concentration. As a result, the detection efficiency increases, leading to a sharp rise in the bright current and higher sensitivity, smaller NEP, and larger *D*\* values. When subjected to different voltages at room temperature for an incident THz frequency of 0.1 THz, the responsivity  $(R_A)$  linearly increases with the applied voltage.

With the applied voltage of 80 V, the  $R_A$  of 70 and 140  $\mu$ m line spacing devices with or without the Au layer are 34 A/W (6.8 MV/W), 17.7 A/W (3.42 MV/W), 6.1 A/W and 3.4 A/W, which is higher than that of a Golay cell  $(0.1 \text{ MV/W})$ . With the applied voltage of 80 V, the NEP is



<span id="page-6-0"></span>**[Figure 7](#page-6-0)** (Color online) Schematic diagram of femtosecond laser direct writing system and sample. (a) Femtosecond laser direct writing processing of the same schematic diagram and (b) the sample picture after processing the pattern (WTe<sub>2</sub> sandwiched Au film). Left: Line spacing of 140  $\mu$ m; right: Line spacing of 70 μm.



<span id="page-6-1"></span>**[Figure 8](#page-6-1)** (Color online) Results of terahertz detection performance parameters of the device. (a) Device noise. (b) Sensitivity. (c) Equivalent noise power. (d) Detection rate *D*\*.

Materials	Frequency	Detection mechanism	$R_{\rm A}$	NEP $(pW/Hz^{1/2})$	Area	Ref
Bi <sub>2</sub> Se <sub>3</sub>	$0.3$ THz	<b>LSP</b>	$0.29\times10^{-2}$ V/W	0.36	Nano	$[24]$
AlGaN/GaN	$0.5$ THz	<b>FET</b>	10 V/W	25	Nano	$[25]$
PtTe <sub>2</sub>	0.12 THz	<b>FET</b>	1400 V/W	10	Nano	$[26]$
PdTe <sub>2</sub>	$0.3$ THz	<b>PCE</b>	$1.3\times10^{-8}$ V/W	57	Nano	$[27]$
Black phosphorus	0.29 THz	<b>PTE</b>	297 V/W	138	Nano	$[28]$
InSb	$0.03$ THz	<b>SPP</b>	$2.6 \times 10^5$ V/W	0.02	Micron	$[22]$
Golay cell (Commercial)	$0.1$ THz	Thermal	$1 \times 10^5$ V/W	140	Millimetre	$[29]$
Bolometer (Commercial)	$0.1$ THz	Thermal	$2.4 \times 10^5$ V/W (4.2 K)	0.25	Millimetre	$[30]$
PbS micro-wheel array	$0.28$ THz	<b>LSP</b>	$4.56$ A/W	0.0188	Millimetre	$[23]$
	$0.14$ THz		3.12 A/W	0.661		
WTe <sub>2</sub> microdisk array	$0.1$ THz	<b>LSP</b>	8.78 A/W	0.74	Millimetre	$[31]$
$MoTe2$ nanofilm	$0.1$ THz	<b>PCE</b>	$4 \text{ A/W}$	9.74	Millimetre	$[32]$
Te	0.305 THz	PCE	9.83 A/W	0.6	Nano	$[33]$
$Bi_{88}Sb_{12}$	$0.14$ THz	Thermoelectric	$12 - 20$ mV/W	770	Micron	$[34]$
GO-Bi	0.22 THz	Thermoelectric	$0.226$ V/W	1330	Micron	$[35]$
SiGe	$0.9$ THz	<b>HBT</b>	$0.65$ A/W	19	Nano	[36]
AlGaN/GaN	0.74 THz	<b>HEMTs</b>	$0.56$ A/W	-	Micron	$[37]$

<span id="page-7-1"></span>**[Table 1](#page-7-1)** Terahertz detectors at room temperature during recent 3 years<sup>[a\)](#page-7-2)</sup>

<span id="page-7-2"></span>a) PCE: Photoconductive effect; EIW: Electromagnetic induction well; PTE: Photothermoelectirc; FET: Field effect transistor; SPP: Surface plasmon polariton; LSP: Localized surface plasmon; HEMTs: High-electron-mobility transistors; HBT: Heterojunction bipolar transistor

0.1 THz EIW/LSP/Micro-cavity  $\frac{34 \text{ A/W or}}{6.8 \times 10^5 \text{ M}}$ 

1.8, 2.7, 11.1 and 14.3 pW/Hz<sup>1/2</sup> for the 70 and 140 µm line spacing devices with the Au layer which just 1/50 to 1/77 of the commercial Golay cell (140 pW/Hz<sup>172</sup>) [\[26\].](#page-8-17) The  $D^*$  of the rating and spiral electrode devices are  $2.95 \times 10^{10}$ ,  $1.96 \times$  $10^{10}$ , 0.49  $\times$  10<sup>10</sup> and 0.38  $\times$  10<sup>10</sup> cm Hz<sup>1/2</sup>/W at the applied voltage of 80 V.

WTe<sub>2</sub> crystalline film<br>direct-write devices

The response rate of devices with line spacing of 70 μm, with or without an Au nanofilm, was tested and yielded current response times of 80 and 93 ms, respectively. For



devices with line spacing of 140 μm, with or without an Au nanofilm, the response times were 103 and 115 ms. It can be observed that the response time decreases as the line spacing decreases, indicating reduced carrier diffusion freedom in the plane. Additionally, the presence of the Au film enhances carrier concentration on the device surface, resulting in shorter response times.

 $6.8 \times 10^5$  V/W 1.8 Millimetre This work

Based on the advantages of reproducibility, mass production and high-efficiency detection at room temperature, we have compared terahertz detectors in the past three years, taking into account factors such as preparation and detection performance (responsivity and equivalent noise power). Our proposed solution involves a microcavity structure comprising an annealed crystalline Weyl-semimetallic active layer and an Au nano-layer, along with an additional subwavelength structure to introduce EIW and LSP effects. This combination enhances the device's responsiveness to 6G signals, providing an effective and significant solution for high-performance terahertz detection technology.

#### **4 Conclusion**

<span id="page-7-0"></span>[Figure 9](#page-7-0) (Color online) Response time test chart of the four devices. To meet the demand for ultra-sensitive detectors for 6G IoT

edge intelligence technology, we prepared large-area Weylsemimetal layers by magnetron sputtering, obtained highquality Weyl-semimetal active layers by controlled annealing conditions, and then prepared thin Au layers as microcavity reflection layers, processed 2D microstructure patterns by femtosecond laser direct writing technology, and introduced both EIW and LSP. The detection sensitivity is 34 A/W for the preferably processed 36 nm Au film and 150 $\degree$ C, 1 h annealing time of WTe<sub>2</sub> film, 90 $\degree$  folding line with a fixed line width of 20 μm and a line spacing of 70 μm. The equivalent noise power NEP is 1.8  $pW/Hz^{1/2}$  and the response time is 80 ms. The proposed scheme offers the potential to manufacture high-performance terahertz detectors with industrial production potential proposed and provides an effective technical solution for the development of 6G technology.

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